1. Equipment: Plasma-enriched chemical vapour deposition (PECVD) system
2. Indentor: Dr. Shiv Govind Singh
3. Location: Nano centre, workshop, ODF
4. Preference of slot types (mention minimum time required for one time use):
5. Hours: 3 hr.
6. Samples: we are accepting samples of up to 4” size for defects measurements
7. Tentative cost per slot/sample: 1000/slot

(please give a reasonable estimate comparing the instrument costs with other facilities at other IITs/Research centres)

1. Rules and guidelines:
* Samples/materials allowed in the equipment: Si, Glass, Other CMOS and MEMS compatible materials
* Restricted materials/samples in the equipment: Non CMOS compatible materials
* The user will have to prepare the sample, but she/he may consult the operator for choosing an appropriate technique. The maximum substrate height is 4 mm. Unclean/Contaminated substrates are not allowed. Contact operator one day in advance about the cleaning procedure.
* To reduce chances, the substrates should be preserved in a vacuum a desiccator after cleaning till it is inserted in the Evaporation for observation. This will improve adhesion between the substrate and the thin film
* Slot will be allotted based on current availability and the user will be notified by email about it at least three days prior to the scheduled slot.